AMENDMENTS TO THE SPECIFICATION

Pages 9-10, paragraph number 23 should be replaced with:

[0023] According to an embodiment of the present invention, energy beam source 230 could comprise a pulsed laser. For example, contaminant layer 213 could comprise a 5 angstrom thick layer of water and organic materials (which is similar to contamination layers often formed on modern thin film layers during production). A number of pulses or even a single pulse from a 5-100μJoule laser having a 1-1000ns pulse duration could then heat the desired portion of contaminant layer 213 to between roughly 300°C to 1000°C, which is a temperature range sufficient to vaporize that portion of contaminant layer 213. According to another embodiment of the present invention, energy beam source 230 could comprise a Q-switched laser delivering a relatively high peak power, such as a frequency-doubled or tripled YAG (yttrium aluminum garnet) laser operating at wavelengths of 532nm or 355nm, respectively. According to another embodiment of the present invention, other types of pulsed lasers operating at different wavelengths might be used including pulsed diode or alexandrite lasers. According to another embodiment of the present invention, a continuous laser, such as an argon-ion laser, could be externally modulated (such as with an acousto-optic or electro-optic modulator) to produce a pulse. According to another embodiment of the present invention, energy beam source 230 could include focusing optics such as an optical fiber 232 (shown using dotted lines) and a lens system to deliver a beam of the desired size and energy to spot 214a from a remote location, i.e., the optional optical fiber 232 could transmit energy beam 231 from a remote beam generator to spot 214a. According to another embodiment of the present invention, energy beam source 230 could comprise a

flashlamp coupled to focusing optics to direct the high intensity light to the desired area on contaminant layer 213.